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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE



Application of:
Maria Ronay
Serial No.: 09/577,347
Filed: May 24, 2000
For: Selective Polishing with
Slurries Containing
Polyelectrolytes
Art Unit: 1765
Examiner: Perez Ramos, V.
Atty Docket: YOR920000109US1

RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents
Washington, D.C. 20231

Sir:

This is in response to the Office Action dated September 21, 2001.

Claims 1-21 are now in the application. Applicant hereby elects the invention directed to the polishing method and identified by the Examiner as Group II. Claims 13-21 are drawn to the elected invention. Claims 1-12 are drawn to non-elected invention and may be cancelled by the Examiner upon the allowance of the claims directed to the elected invention.

In view of the above, consideration and allowance are, therefore, respectfully solicited.

In the event the Examiner believes an interview might serve to advance the prosecution of this application in any way, the undersigned attorney is available at the telephone number noted below.

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The Director is hereby authorized to charge any fees, or credit any overpayment, associated with this communication, including any extension fees, to Deposit Account No. 22-0185.

Respectfully submitted,


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Date: 10-22-01